# WK-Series (White Knight<sup>™</sup>) Gas Purifiers

## **Overview**

NANOCHEM® WK-Series (White Knight™) purifiers offer the highest lifetimes and the best impurity removal efficiencies in a very economical design. The in-line design enables a very compact footprint and allows drop-in replacement of competing hardware designs. The WK-Series is available in a number of sizes for point-of-use applications to bulk gas purification.

## **Features and Benefits**

- For point-of-use to bulk flow specialty gas purification
- Highest Lifetimes
- Best Impurity Removal Efficiencies
  - Removes critical contaminants to sub part-per-trillion levels
- Enhances manufacturing process economy and improves equipment performance
- Provides consistently high purity gas under fluctuating inlet impurity conditions
- Improves component lifetime and reduces particle generation by removing moisture from corrosive gases
- Compact footprint; inline design
- Easy to install and operate
- No heating or cooling required
- Quick start up
- All metal parts, type 316L stainless steel, or Nickel 200
- Economical, low cost of ownership





# **Impurities Removed**

Gas Type	Contaminants	Outlet Purity			
Inerts - Nitrogen (N <sub>2</sub> ),	H <sub>2</sub> O	< 86 ppt			
Argon (Ar), other inerts	$O_2$	< 50 ppt			
	CO	< 100 ppt			
	CO <sub>2</sub>	< 10 ppt			
	Benzene	764 ppq			
	Toluene	938 ppq			
	Ethylbenzene	746 ppq			
	m, p - Xylene	426 ppq			
	o - Xylene	689 ppq			
	TMDSO	697 ppq			
	Refractories*	< 697 ppq			
	H <sub>2</sub>	< 1 ppb			
Ammonia (NH <sub>3</sub> )	H₂O	< 45 ppb			
	$O_2$	< 0.1 ppb			
	CO <sub>2</sub>	< 11 ppb			
	Carbamate	< 11 ppb			
	GeH₄	< 1 ppb			
	SiH <sub>4</sub>	< 3 ppb			
	Siloxanes	< 40 ppb			
	Metals				
	Al	< 0.6 ppb			
	Cu	< 0.27 ppb			
	Fe	< 0.8 ppb			
	K	< 0.35 ppb			
	Na	< 0.27 ppb			
	Si	< 1.3 ppb			
	W	< 0.11 ppb			
	Zn	<0.27 ppb			
	Zr	< 0.11 ppb			
	Hydrocarbons from Liquid NH <sub>3</sub>				
	Napthenic and Paraffins	85% removal			
	Ethyl Benzene	96% removal			
	Dissolved other HC	<200 ppb			
	Hydrocarbons from Ga				
	n-Butane	<30 ppb			
	Ethylbenzene	<30 ppb			
Carbon Dioxide (Purifier	Isopropyl Alcohol	200 ppt			
material HCX)	Acetone	93 ppt			
	Propene	< 1 ppt			
	Ethanol	< 1 ppt			
	Carbon Disulfide	< 1 ppt			
	Hexane	< 1 ppt			
	Benzene	< 1 ppt			

Gas Type	Contaminants	<b>Outlet Purity</b>				
Carbon Dioxide	Heptane	< 1 ppt				
(Purifier material HCX) continued	Toluene	< 1 ppt				
continued	m,p-Xylene	< 1 ppt				
	o-Xylene	< 1 ppt				
	Ethyl Toluene	< 1 ppt				
	1,3,5-Trimethyl Benzene	< 1 ppt				
	1,2,4-Trimethyl Benzene	< 1 ppt				
	DichloroBenzene	< 1 ppt				
Silane (SiH <sub>4</sub> )	H₂O	< 100 ppt				
	O <sub>2</sub>	< 100 ppt				
	CO <sub>2</sub>	< 100 ppt				
	CO**	< 1 ppb				
	Chlorosilanes, disilane, siloxanes, arsine, phosphine					
Hydrogen (H <sub>2</sub> )	H <sub>2</sub> O	< 100 ppt				
	O <sub>2</sub>	< 100 ppt				
	CO <sub>2</sub>	< 100 ppt				
Methane (CH <sub>4</sub> )	CO**	< 1 ppb				
Ethane (C <sub>2</sub> H <sub>6</sub> ), other HC	NOx, SOx, H2S					
Sulfur Hexafluoride (SF <sub>6</sub> )	H₂O in inert gas	< 100 ppt				
	O₂ in inert gas	< 100 ppt				
	CO <sub>2</sub> in inert gas	< 100 ppt				
Carbon Tetrafluoride	H₂O in sulfur hexafluoride	< 10 ppb				
(CF <sub>4</sub> )	O <sub>2</sub> in sulfur hexafluoride	< 10 ppb				
Other Fluorocarbons	H₂O in sulfur hexafluoride	< 10 ppb				
	O <sub>2</sub> in sulfur hexafluoride	< 10 ppb				
Oxygen (O <sub>2</sub> ),	H₂O	< 10 ppb				
Carbon Dioxide (CO <sub>2</sub> ),	H <sub>2</sub> O	< 10 ppb				
Nitrous Oxide (N <sub>2</sub> O)	H <sub>2</sub> O	< 10 ppb				
Carbon Monoxide (CO)	Metal Carbonyls: Fe, Ni					
Corrosives (HCI, HBr, Cl <sub>2</sub> )	H₂O in inert gas	< 1 ppb				
SiH <sub>2</sub> Cl <sub>2</sub> , SiHCl <sub>3</sub> , BCl <sub>3</sub> )	H₂O in HBr	< 100 ppb				
	H₂O in HCl	< 100 ppb				
	Volatile Metals***					
	Мо	< 4 ppb				
	Ti	< 13 ppb				
	Fe(CO)5	< 50 ppb				
Impurity removal depends on purifier material and incoming gas specification						

Metals removal as demonstrated by intrinsic resistivity measurements on wafer grown by TCS: Without MTX Purifier: <200 ohm-cm

With MTX Purifier: > 2500 ohm-cm and total metals on water <1E10 atoms/cm2

Impurity removal depends on purifier material and incoming gas specification
\*Refractories as TMDSO (Tetramethyldisiloxane)
\*\*CO is removed efficiently by OMX & OMX-Plus<sup>TM</sup> media at low flow rates (recommend 1/10 of normal flow rate)

<sup>\*\*\*</sup>Metals removed as measured on wafer via VPD-ICPMS:

Al, Ca, Cr, Fe, Mg, Ni, K, Na, Zn

# **Analytical Characterization of NANOCHEM® NHX™ Purifier**

Impurity/Matrix	Capacity (L/L)	Efficiency (ppb)	Challenge (ppm)	Method	
H₂S in He	6	<0.3 (D/L)	50	GC-AED	
H₂S in Ar	31	<0.3 (D/L)	35	API-MS	
H <sub>2</sub> S in NH <sub>3</sub>	25	<45 (D/L)	1000	FTIR	
CO <sub>2</sub> in He	5	<11 (D/L)	500	GC-DID	
CO <sub>2</sub> in NH <sub>3</sub>	_	<11 (D/L)	25	GC-DID	
GeH <sub>4</sub> in N <sub>2</sub>	_	<0.1 (D/L)	2.5	API-MS	
SiH <sub>4</sub> in N <sub>2</sub>	_	<0.1 (D/L)	2.5	API-MS	
Siloxanes in N <sub>2</sub>	_	<-0.1 (D/L)	(trace)	API-MS	
GeH₄ in NH₃	_	<0.5 (D/L)	1.0	GC-AED	
SiH <sub>4</sub> in NH <sub>3</sub>	_	<1 (D/L)	1.0	GC-AED	
TEOS (siloxane) in NH <sub>3</sub>	_	<40 (D/L)	640	GC-DID	
O <sub>2</sub> in NH <sub>3</sub>	_	<50 (D/L)	100	GC-DID	

## **Purifier Models**

	WK-70 WK-75	WK-300	WK-500	WK-700	WK-2500	WK-5000
Media bed volume	50 ml 55 ml	300 ml	500 ml	700 ml	2500 ml	5000 ml
Maximum flow rate (in nitrogen), slpm (NM³/hr)	10 (0.6)	75 (4.5)	150 (9.0)	225 (13.5)	500 (30)	800 (48)
Pressure Drop at maximum flow rate (psi), tested in N <sub>2</sub> at 90 psi inlet	< 1 (<0.007 MPa)	TBD	< 5 (<0.04 MPa)	< 7 (<0.05 MPa)	< 5 (<0.04 MPa)	< 4 (<0.03 MPa)
Max permissible operating pressure, psi	1000 (7 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)	500 (3.5 MPa)



# **Specifications**

- 0.003 µm filter with 99.999999% retention (PTFE or 316L SS)
- Internal surface finish < 15 μin Ra
- Maximum operating temperature is 40°C

## **Connections**

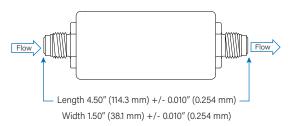
• Male inlet and outlet connections, 1/4" VCR - compatible

# **Options**

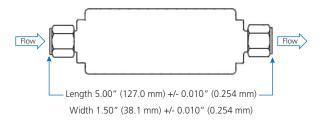
- Inlet and outlet isolation valves
- Three-valve manifold with isolation and bypass valves allows disconnection of purifier without interrupting process gas flow



# **Dimensions**

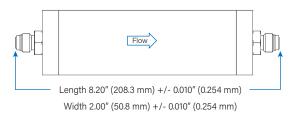


#### **NANOCHEM®** Purifier Model WK-70



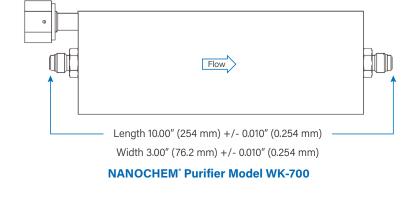
#### **NANOCHEM®** Purifier Model WK-75

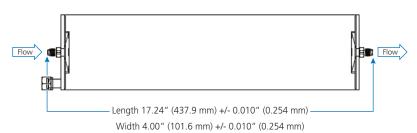
\*actual media volume is 55 ml



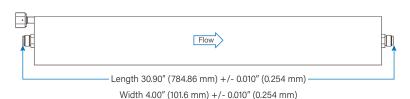
### **NANOCHEM®** Purifier Model WK-300







#### **NANOCHEM®** Purifier Model WK-2500



#### **NANOCHEM®** Purifier Model WK-5000

Dimensions in inches (mm)

Note: Purifiers are shown in horizontal position for illustration purposes only. Purifiers must be installed vertically.

Models WK-75, WK-300, WK-500, WK-700, WK-2500 and WK-5000 have a 0.003  $\mu m$  particle filter.

### Nanochem Purification

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